

ABSTRACT

The present invention provides a semiconductor cleaning liquid which contains isopropyl alcohol, while having a mass ratio of t-butyl alcohol of 1 ppm or less relative to the isopropyl alcohol. The present invention also provides a method for producing a semiconductor cleaning liquid, the method comprising a first distillation step in which a crude aqueous isopropyl alcohol solution that contains t-butyl alcohol as an impurity is supplied to a starting material supply plate of a first distillation column, and a first liquid distillate which contains a low boiling point impurity that has a lower boiling point than isopropyl alcohol is extracted from the column top of the first distillation column, while extracting a first bottom liquid from the column bottom of the first distillation column. In the first distillation step, a fluid containing water is supplied, from the outside of the first distillation column, to a predetermined plate that is above the starting material supply plate by two or more theoretical plates so that the water content in the liquid phase is 15% by mass or more at three or more theoretical plates among the plates of the first distillation column from the starting material supply plate to the column top.